

# Plasma Reactor (Barrel Chamber)

Compact, Barrel Type, Low Temperature Ashing Device

## PR500/510

High-frequency  
Output

50~500W

Reaction  
chamber

ø215×305mm

Designed with large chamber size made of quartz considered almost completely resistant against most plasma processes



PR500 (Manual version)



PR510 (Touch panel version)

### ■ Features

- Compact, space saving design with oscillation section integrated with a portion of the chamber
- Outstanding operability and safety with the automatic tuning system as standard component
- Equipped with a large quartz chamber (ø215mm) which can process big testing samples

### ■ Applications

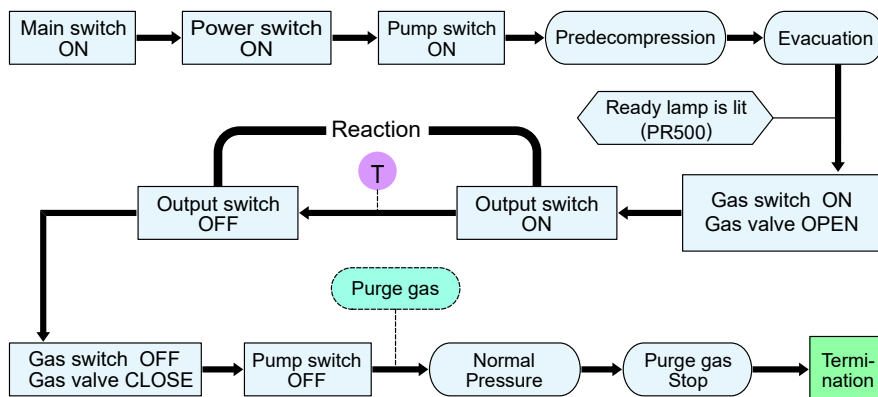
- Removal of photoresist
- Cleaning of parts
- Surfactant treatment
- Micro polishing
- Corresponds to wafer and glass substrate

### ■ Specifications

Product code	215007	215012
Model	PR500 (Flow meter)	PR510 (Mass flow meter)
Method	Barrel type chamber direct plasma (DP)	
High frequency output	Max. 500W	
Oscillating frequency	13.56MHz	
Tuning method	Automatic tuning	
Reaction chamber	Made of quartz, ø215×305mm	
Reaction gas	Dual system (O <sub>2</sub> / CF <sub>4</sub> )	
Control system	Manual	Automatic touch panel
Piping material	Stainless steel, Teflon	
Gas inlet	1/4" swagelok	
Vacuum pump inlet	NW25	
External dimensions	W438×D520×H760mm	W520×D630×H760mm
Weight	Approx. 53kg	Approx. 70kg
Power source (50/60Hz)	AC115V / AC220V Single phase with step-down transformer	AC220V~AC415V Three phase with step-down transformer
Standard accessories	Vacuum grease×1 pc. O-ring for reaction chamber×1 pc.	
Optional accessories	Frame for wafers (2, 3, 4, 5 inches) Multi-purpose angled frame Aluminum etching tunnel (ø180 max.) Vacuum pump (250L/min. or more)	

External dimensions do not include projections.

## Operation Flowchart



## Control Panel

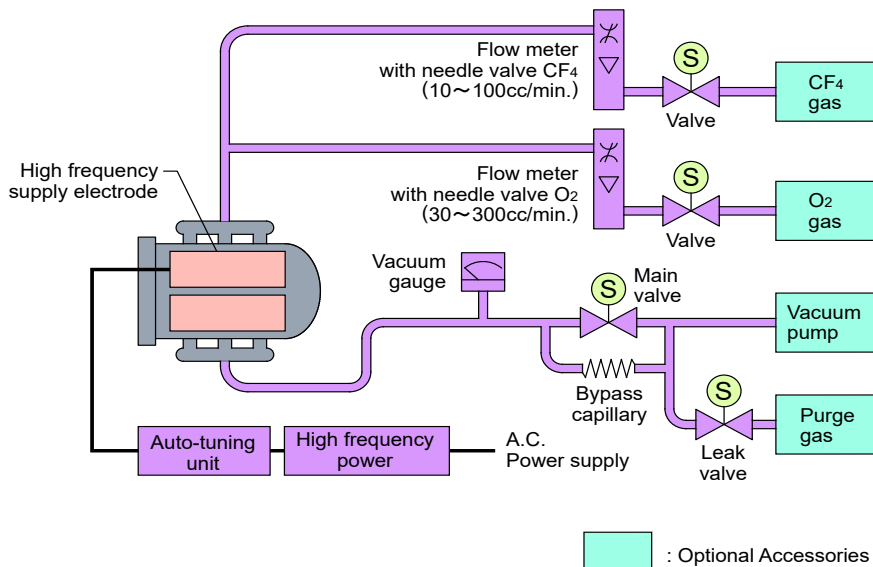


## Chamber

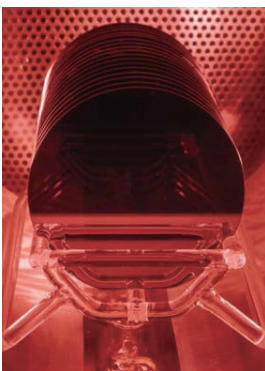


ø215mm large caliber chamber

## Piping System (PR500/510)



## Wafer Ashing



The gas plasma equipment has a wide range of applications from ashing, etching, dry cleaning, etc.